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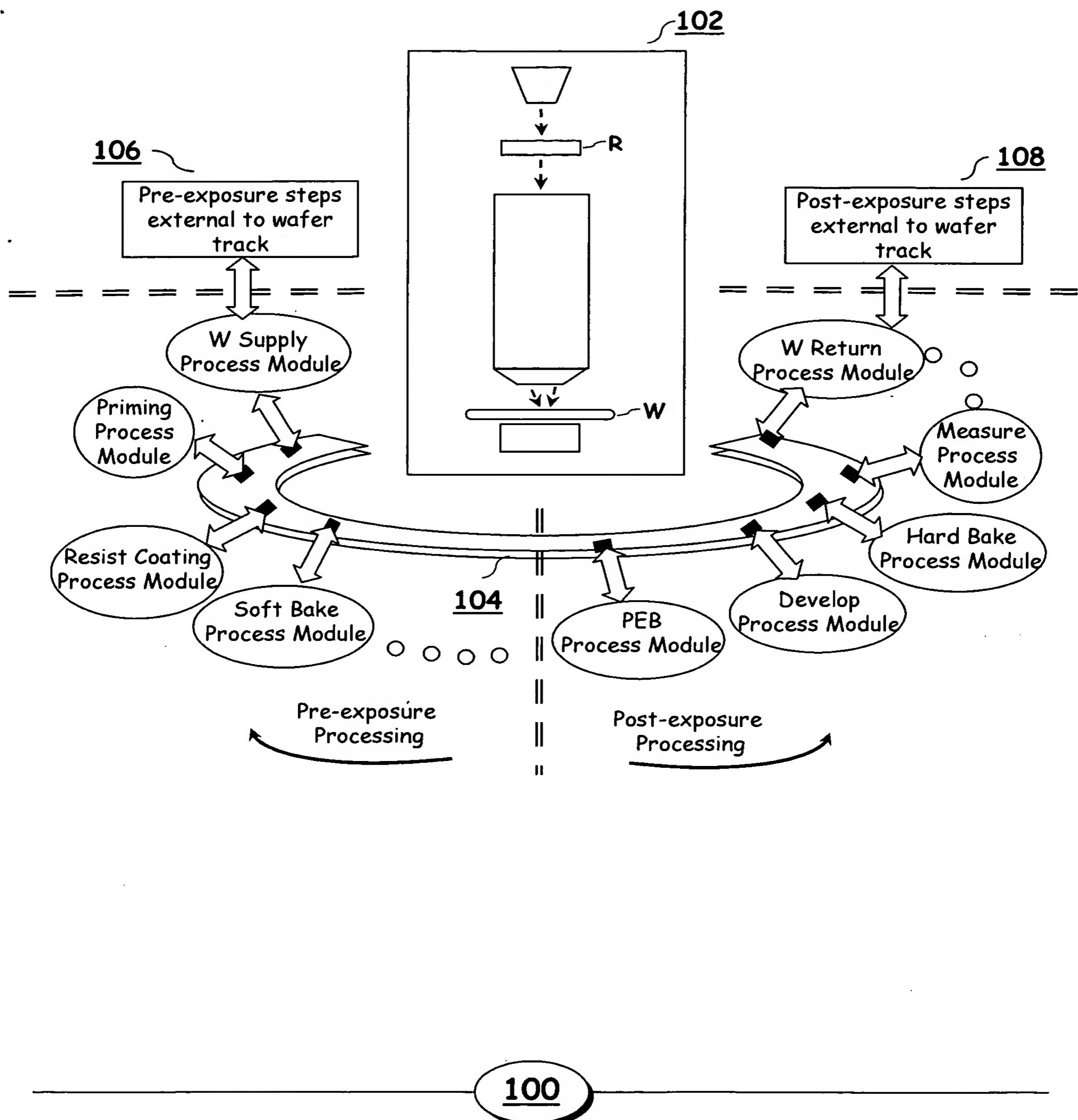
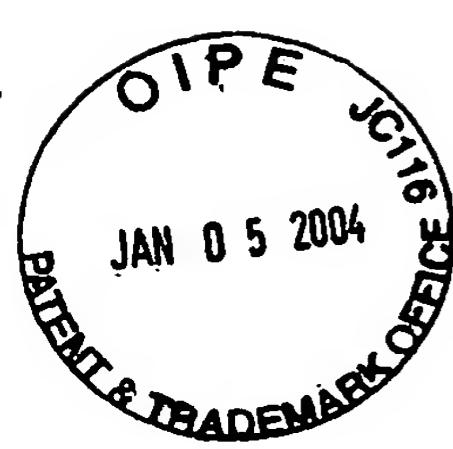


FIG. 1A

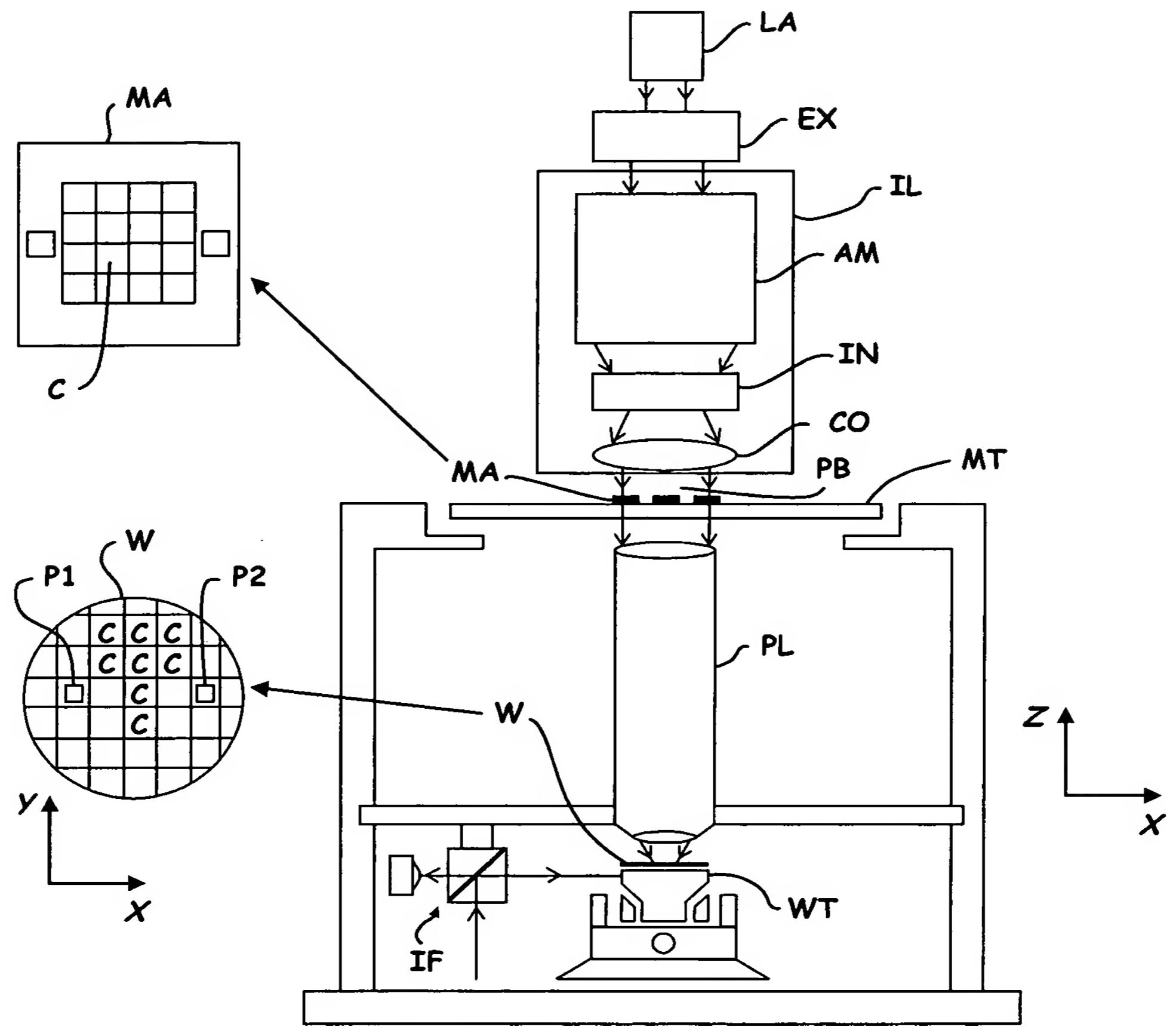


FIG. 1B

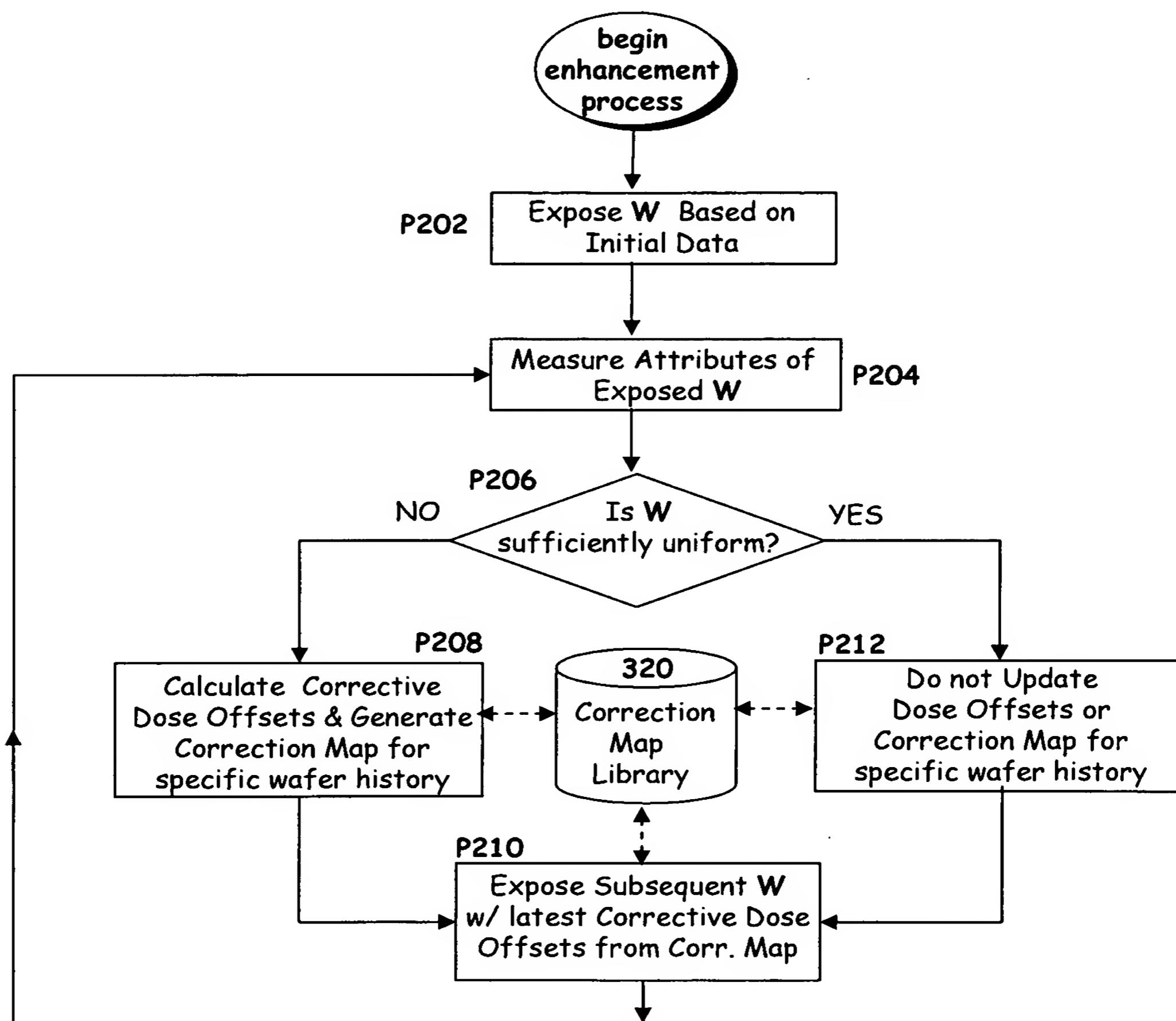
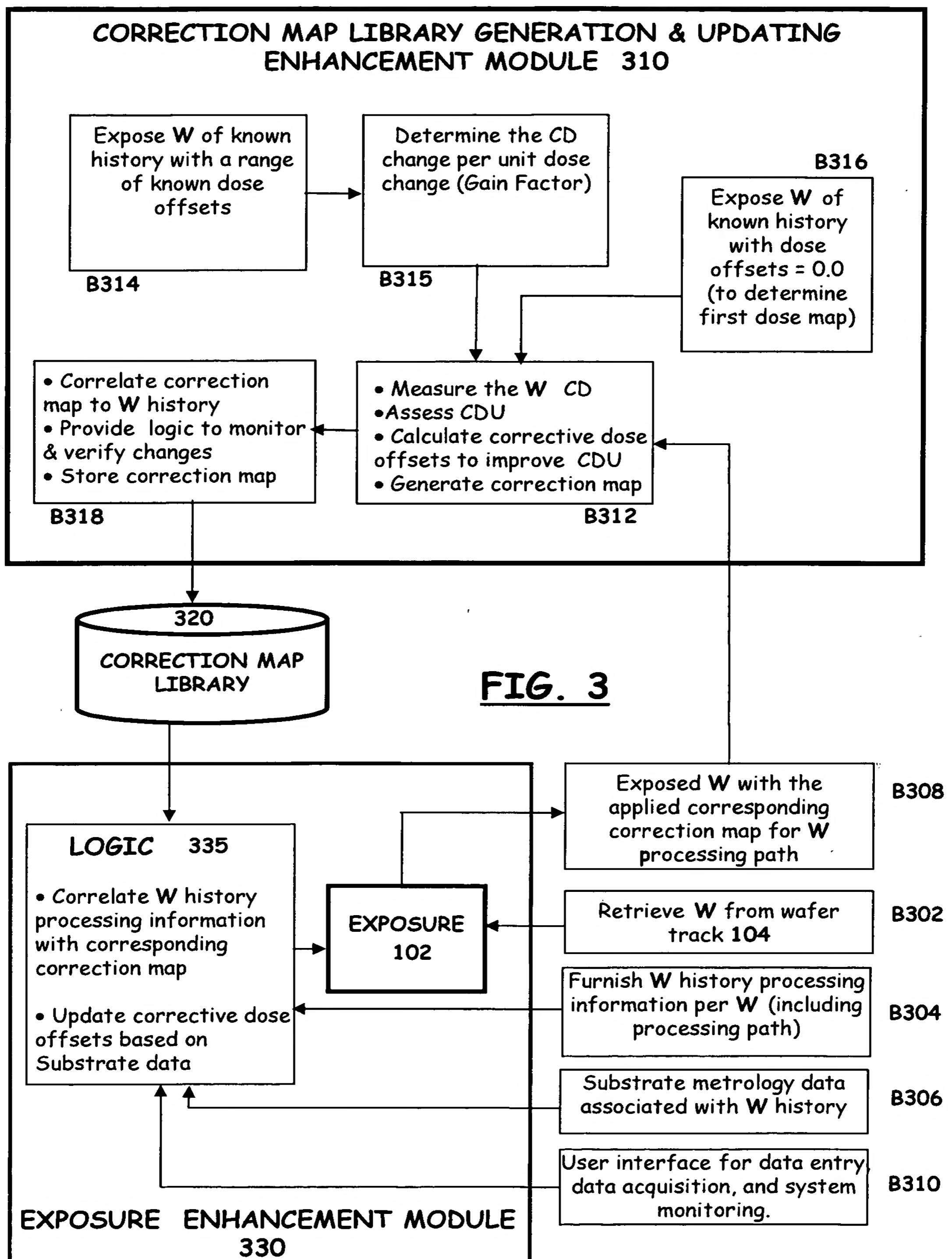
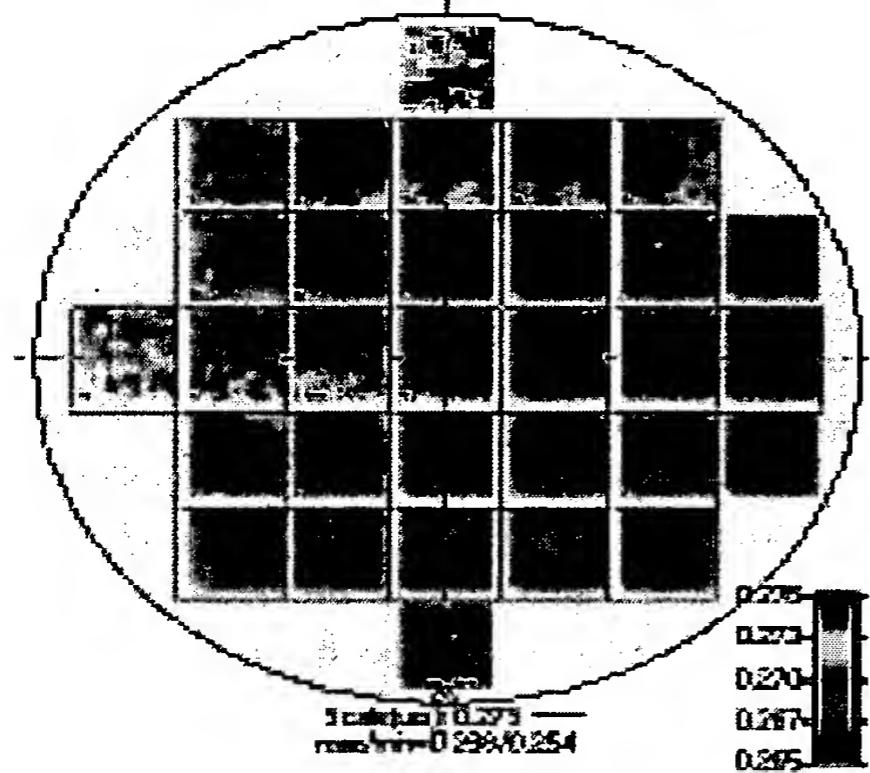


FIG. 2



Examples Pre Exposure Substrate Metrology Data (B306)

Resist thickness



BARC Thickness

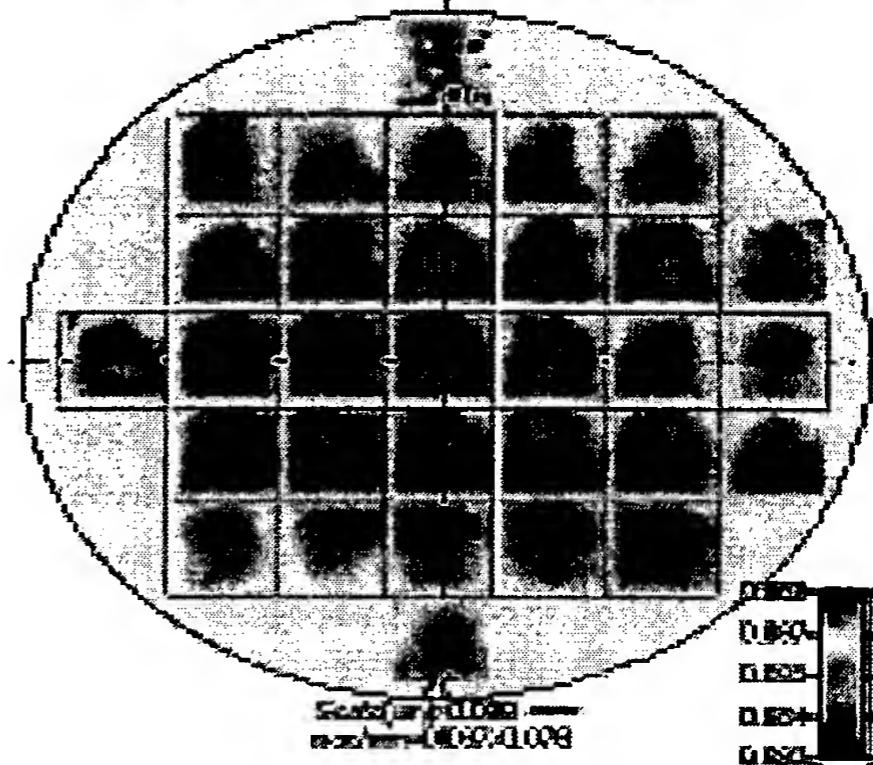


FIG. 4A

FIG. 4B

Example Wafer Dose Layout & Range (B314)

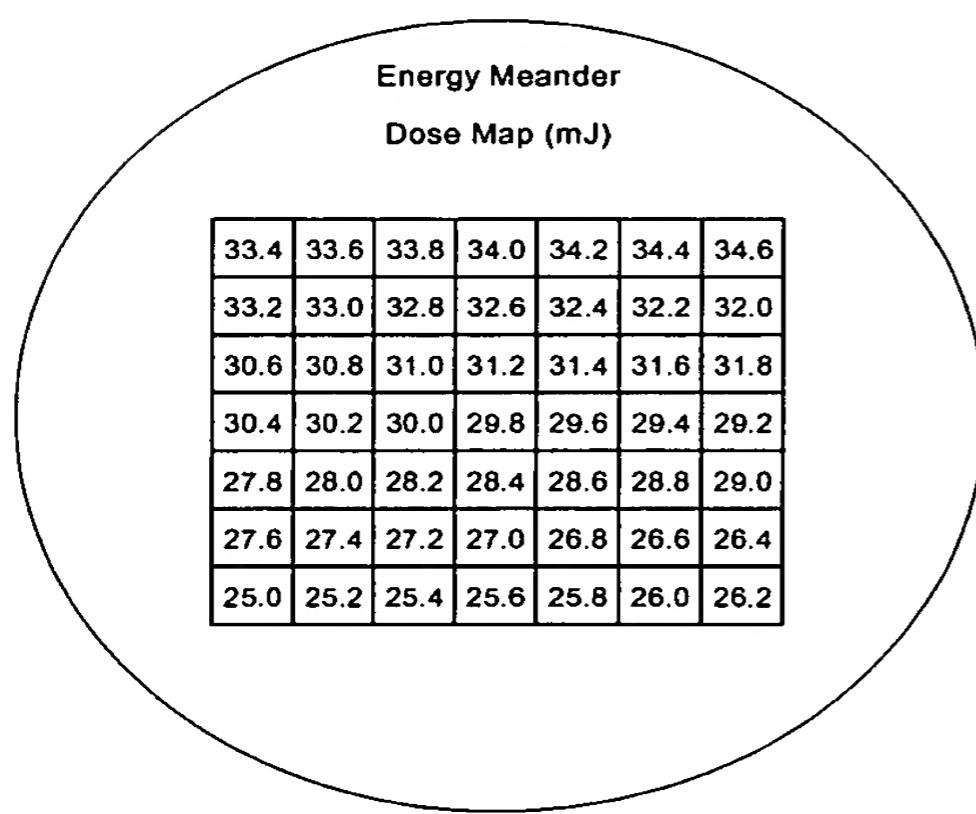


FIG. 4C

Example CD Change per Unit Dose (B315)

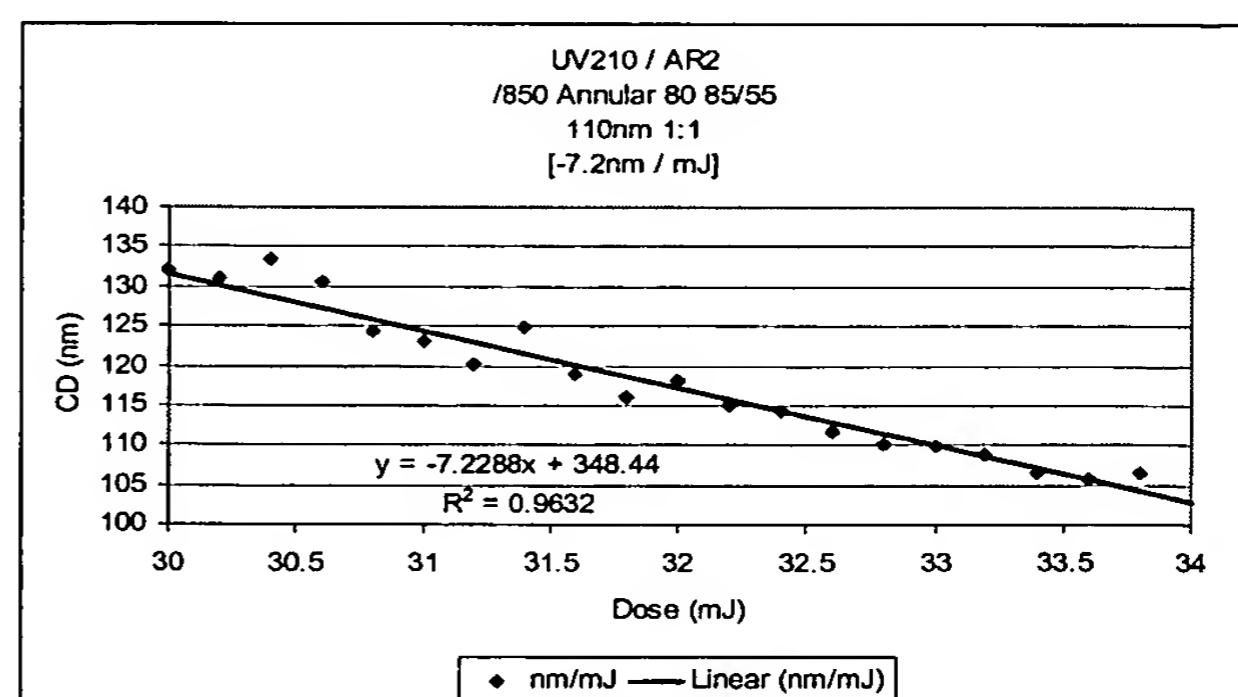


FIG. 4D

Example Initial Dose Map:
Dose Offset = 0 (B316)

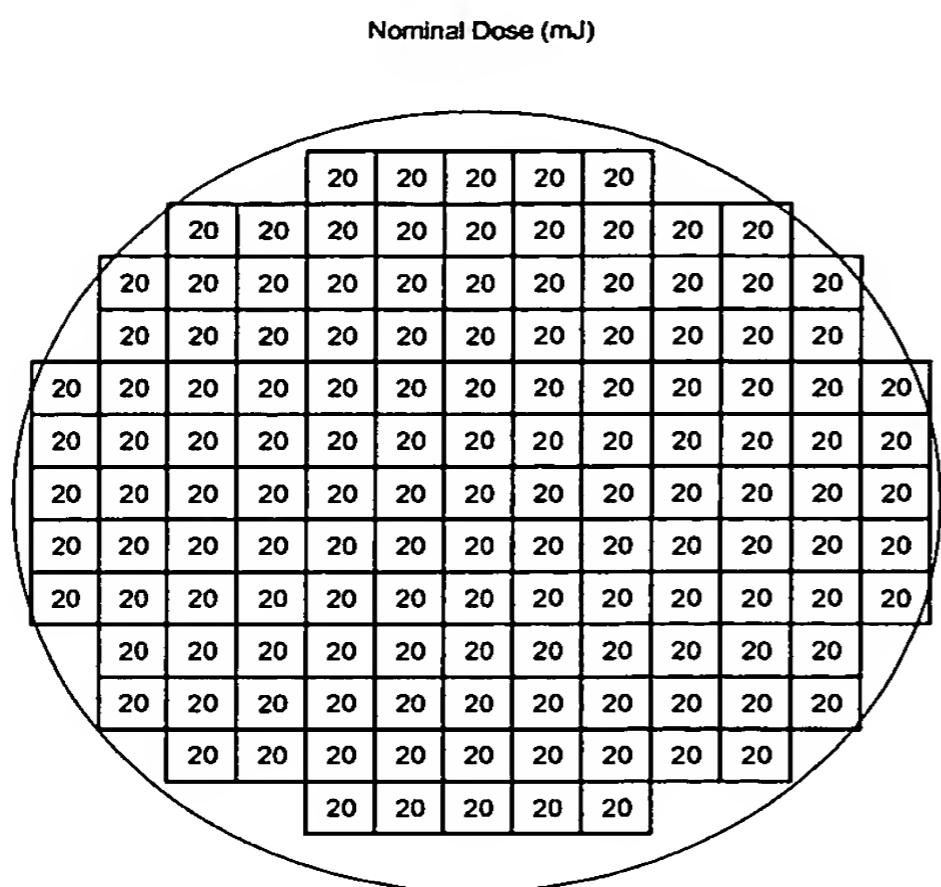


FIG. 4E

Example CD Results:
with Dose Offset = 0 (B312)

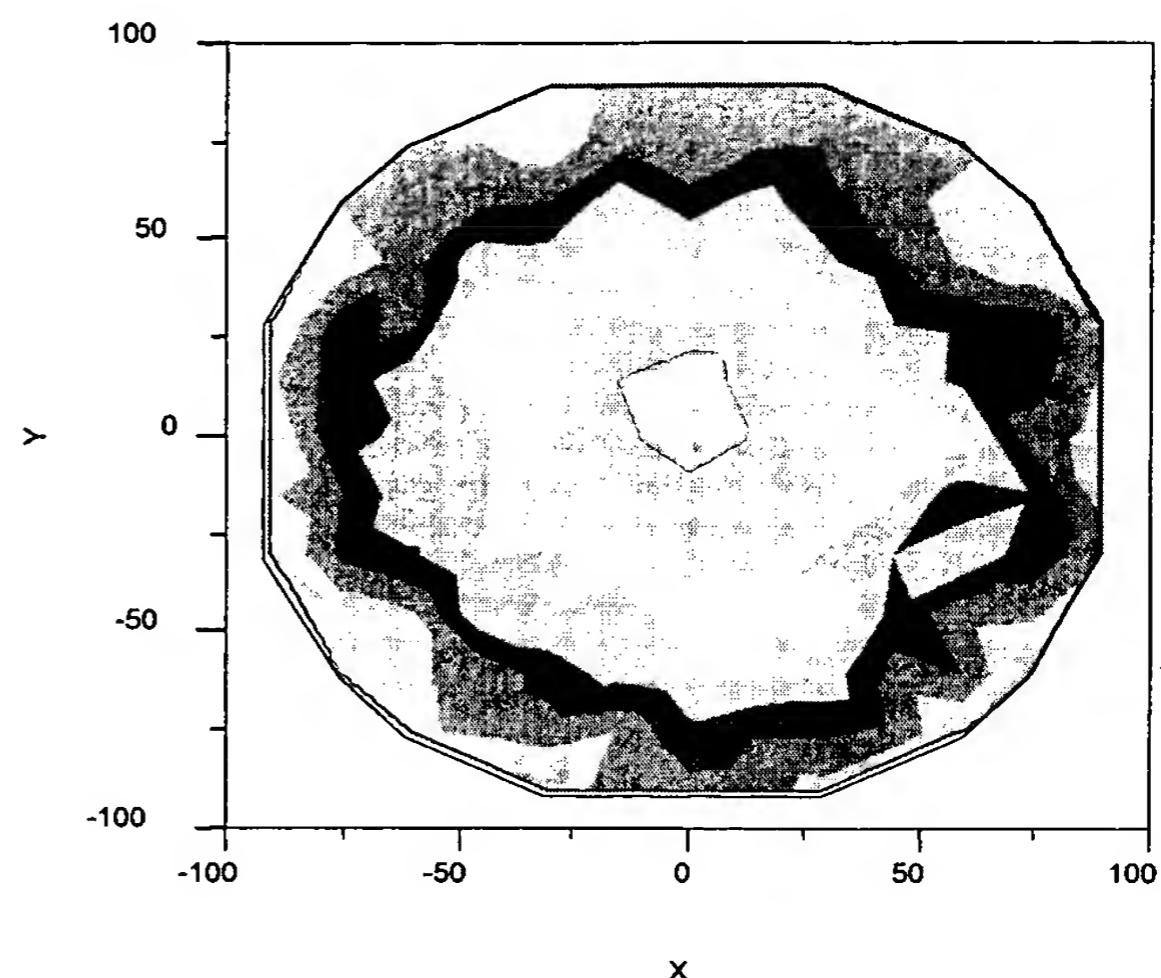


FIG. 4F

Example Wafer Dose Layout with Dose Offset (B308)

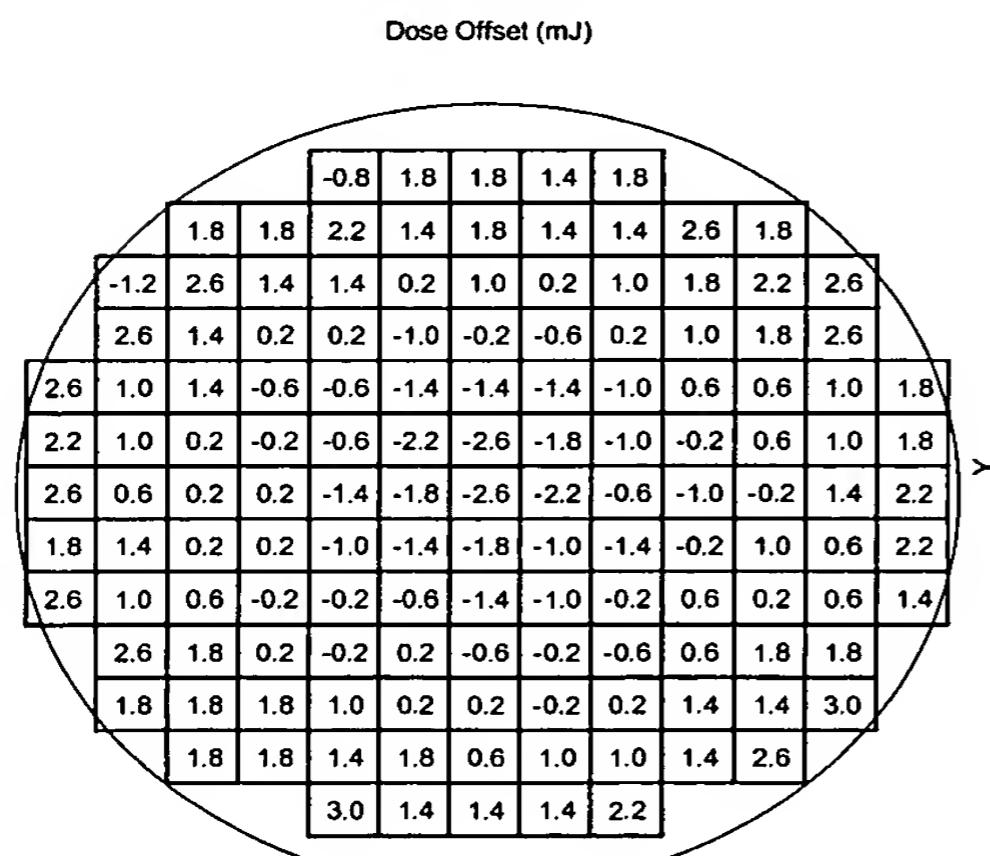


FIG. 4G

Example CD Results:
with Applied Dose Offset (B312)

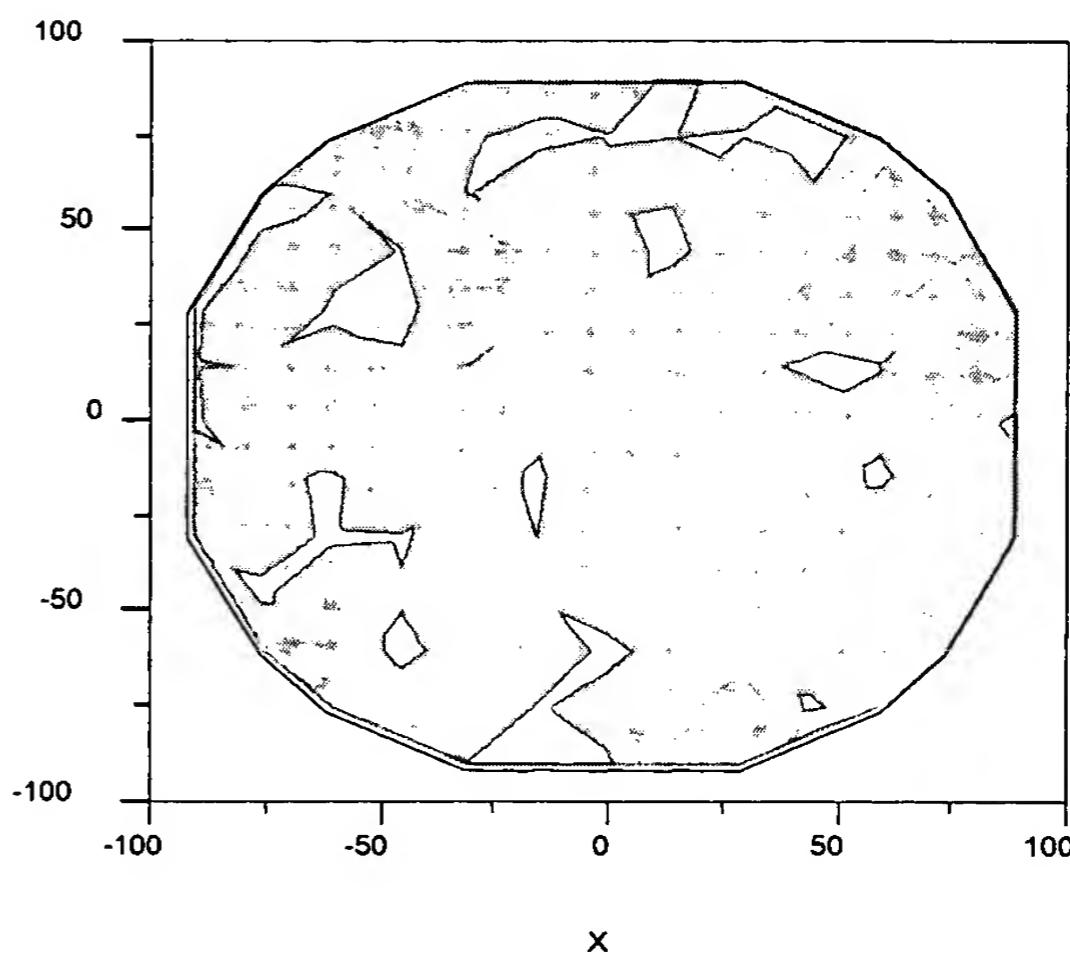


FIG. 4H